AZ® 10XT Photoresist
Thick Positive Novolak Photoresist
For Plating and Etch Applications
AZ® 10XT Photoresist

AZ® 10XT positive photoresist is designed for 5 to 25 micron film thickness in high performance rerouting processes and other plating applications.

Three viscosities are available to cover a variety of film thicknesses.

PFOS free formulation.

Excellent coat capability, 3 to 1 aspect ratios, vertical sidewalls.

Sensitive to g, h and i-line wavelengths

Compatible with both inorganic and organic developers. Shorter develop times can be realized with inorganic developers, however.
AZ® 10 XT Photoresist
Optical Constants (n & k)
AZ® 10XT Photoresist, FT=6 μm
3.0 μm L/S Exposure Latitude on Silicon

Optitrac coat and Bake
SB: 110°C/ 120 sec
Ultratech 1500 gh line stepper
AZ 400K 1:4 / 420 sec immersion @ 23 °C

600 mJ/cm²
650 mJ/cm²
700 mJ/cm²
750 mJ/cm²

800 mJ/cm²

900 mJ/cm²

850 mJ/cm²
AZ® 10XT Photoresist, FT=6 µm
Linearity on Copper @ 850 mJ/cm²

Optitrac coat and Bake
SB: 110°C/120 sec
Ultratech 1500 gh line stepper
AZ 400K 1:4 / 420 sec immersion @ 23 °C

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AZ® 10XT Photoresist, FT=6 μm
CH Linearity on Copper @ 800 mJ/cm²

Optitrac coat and Bake
SB: 120°C/120 sec
Ultratech 1500 gh line stepper
AZ 400K 1:4/420 sec immersion @ 23 °C
AZ® 10XT Photoresist, FT=12 µm
Linearity on Silicon @ 1425 mJ/cm²

Film Thickness: 12 µm
Optitrac Coat and Develop
SB: 110°C/ 180 sec
Ultratech 1500 gh line Stepper
AZ 400K 1:4, 260 sec continuous spray @ 27 °C
AZ® 10XT Photoresist, FT=24 µm
Depth of Focus @ 2000 mJ/cm², 10.0 µm L/S

-14.0 µm

-12.0 µm

-10.0 µm

-8.0 µm

Optitrac Coat and Bake
SB: 1st layer 110°C/ 80 sec
2nd layer 115°C/180 sec
Ultratech 1500 gh line Stepper
AZ 400K 1:4, 600 sec continuous spray @ 27 °C

-6.0 µm

2.0 µm

0.0 µm

-2.0 µm

-4.0 µm

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